

L Number	Hits	Search Text	DB	Time stamp
1	14	"projection ion beam lithography"	USPAT; US-PGPUB; EPO; JPO	2004/07/11 19:50
2	0	5264981.pn. and width	USPAT	2004/07/11 19:51
3	0	5264981.pn. and w	USPAT	2004/07/11 19:51
4	0	5264981.pn. and d	USPAT	2004/07/11 19:53
5	1	5142768.pn. and width	USPAT	2004/07/11 20:08
6	1	6741429.pn.	USPAT	2004/07/11 20:08
7	13	("5079662" "5327313" "5550101" "6077618" "6162582" "6219206" "6297938" "6317302" "6392852" "6404603" "6424508" "6496333" "6525903").pn.	USPAT	2004/07/11 20:10
-	2918	438/3.cccls. 29/592.1.cccls.	USPAT; US-PGPUB; EPO; JPO	2004/07/08 09:29
-	9982	magnetoresistive	USPAT; US-PGPUB; EPO; JPO	2004/07/08 09:21
-	126	magnetoresistive and (438/3.cccls. 29/592.1.cccls. )	USPAT; US-PGPUB; EPO; JPO	2004/07/08 09:22
-	4	("5079662" "5550101" "6077618" "6317302").pn.	USPAT; US-PGPUB; EPO; JPO	2004/07/08 09:24
-	4827	438/3.cccls. 29/592.1.cccls. 438/514.cccls. 438/520.cccls. 438/528.cccls. 438/531.cccls. 360/316.cccls. 360/327.cccls. 360/325.cccls. 428/693.cccls.	USPAT; US-PGPUB; EPO; JPO	2004/07/08 09:30
-	1159	(438/3.cccls. 29/592.1.cccls. 438/514.cccls. 438/520.cccls. 438/528.cccls. 438/531.cccls. 360/316.cccls. 360/327.cccls. 360/325.cccls. 428/693.cccls. ) and (magnet\$8)	USPAT; US-PGPUB; EPO; JPO	2004/07/09 10:56
-	88	((438/3.cccls. 29/592.1.cccls. 438/514.cccls. 438/520.cccls. 438/528.cccls. 438/531.cccls. 360/316.cccls. 360/327.cccls. 360/325.cccls. 428/693.cccls. ) and (magnet\$8)) and (implant\$3 adj3 ion\$2)	USPAT; US-PGPUB; EPO; JPO	2004/07/08 09:47
-	277	ARNETT.INV.	USPAT	2004/07/08 09:47
-	2	ARNETT.INV. and "width control"	USPAT	2004/07/08 09:48
-	0	"profjection ion beam lithography"	USPAT; US-PGPUB; EPO; JPO	2004/07/08 09:48
-	3150	"mr sensor" (magnetoresistive adj2 sensor)	USPAT; US-PGPUB; EPO; JPO	2004/07/08 09:49
-	.1	("mr sensor" (magnetoresistive adj2 sensor)) and "projection ion beam lithography"	USPAT; US-PGPUB; EPO; JPO	2004/07/08 09:49
-	49	("mr sensor" (magnetoresistive adj2 sensor)) and (ion adj3 implant\$8)	USPAT; US-PGPUB; EPO; JPO	2004/07/08 13:06
-	18	(("mr sensor" (magnetoresistive adj2 sensor)) and (ion adj3 implant\$8)) and mask	USPAT; US-PGPUB; EPO; JPO	2004/07/08 10:12
-	3	(US-4308592-\$ or US-5502325-\$).did. or (US-20040027732-\$).did.	USPAT; US-PGPUB	2004/07/08 10:12
-	0	((US-4308592-\$ or US-5502325-\$).did. or (US-20040027732-\$).did.) and (irradiation irradiate)	USPAT; US-PGPUB; EPO; JPO	2004/07/08 10:13
-	2	((US-4308592-\$ or US-5502325-\$).did. or (US-20040027732-\$).did.) and (reduce eliminate)	USPAT; US-PGPUB; EPO; JPO	2004/07/08 10:13
-	1094	((ion adj3 implant\$8) adj4 temperature)	USPAT; US-PGPUB; EPO; JPO	2004/07/08 13:27
-	0	((ion adj3 implant\$8) adj4 temperature) ) same magnetoresistive	USPAT; US-PGPUB; EPO; JPO	2004/07/08 13:07

-	0	((ion adj3 implant\$8) adj4 temperature) ) and magnetoresistive	USPAT; US-PGPUB; EPO; JPO	2004/07/08 13:08
-	5	((ion adj3 implant\$8) adj4 temperature) ) same magnet	USPAT; US-PGPUB; EPO; JPO	2004/07/08 13:08
-	0	((ion adj3 implant\$8) adj4 temperature) ) and (magnetoresistive)	USPAT; US-PGPUB; EPO; JPO	2004/07/08 13:26
-	81	((ion adj3 implant\$8) adj4 "room temperature")	USPAT; US-PGPUB; EPO; JPO	2004/07/08 13:34
-	22	((ion adj3 implant\$8) adj4 "room temperature") ) and (magnet manetoresistive nickel iron NiFe magnetic ferromagnetic)	USPAT; US-PGPUB; EPO; JPO	2004/07/08 13:37
-	45	((ion adj3 implant\$8) adj4 temperature) ) and magnet	USPAT; US-PGPUB; EPO; JPO	2004/07/09 10:51
-	0	4308592.pn. and irradiate	USPAT	2004/07/08 14:13
-	0	4308592.pn. and irradiat\$3	USPAT	2004/07/08 14:13
-	45	((ion adj3 implant\$8) adj4 temperature) ) and magnet	USPAT; US-PGPUB; EPO; JPO	2004/07/09 10:59
-	2	((((ion adj3 implant\$8) adj4 temperature) ) and magnet ) and (tails stringers tail stringer)	USPAT; US-PGPUB; EPO; JPO	2004/07/09 10:51
-	1159	(438/3.cccls. 29/592.1.cccls. 438/514.cccls. 438/520.cccls. 438/528.cccls. 438/531.cccls. 360/316.cccls. 360/327.cccls. 360/325.cccls. 428/693.cccls. ) and (magnet\$8)	USPAT; US-PGPUB; EPO; JPO	2004/07/09 10:56
-	10	((438/3.cccls. 29/592.1.cccls. 438/514.cccls. 438/520.cccls. 438/528.cccls. 438/531.cccls. 360/316.cccls. 360/327.cccls. 360/325.cccls. 428/693.cccls. ) and (magnet\$8) ) and (tail\$1 stringer\$1)	USPAT; US-PGPUB; EPO; JPO	2004/07/09 10:56
-	67744	(ion adj3 implant\$8)	USPAT; US-PGPUB; EPO; JPO	2004/07/09 10:59
-	1146	((ion adj3 implant\$8) ) and (tail\$1 stringer\$)	USPAT; US-PGPUB; EPO; JPO	2004/07/09 10:59
-	67	((ion adj3 implant\$8) ) and (tail\$1 stringer\$)) and (magneto\$8 ferroelectric)	USPAT; US-PGPUB; EPO; JPO	2004/07/09 11:09
-	624	(gmr mmr) and (tail\$1 stringer\$1)	USPAT; US-PGPUB; EPO; JPO	2004/07/09 11:17
-	74	((gmr mmr) and (tail\$1 stringer\$1)) and sputter\$3	USPAT; US-PGPUB; EPO; JPO	2004/07/09 11:36
-	1	5949623.pn. and (photolithographic)	USPAT; US-PGPUB; EPO; JPO	2004/07/09 11:35
-	0	5949623.pn. and (electron)	USPAT; US-PGPUB; EPO; JPO	2004/07/09 11:35
-	0	5949623.pn. and (stencil)	USPAT; US-PGPUB; EPO; JPO	2004/07/09 11:35
-	3	(US-6111722-\$ or US-5949623-\$ or US-5528440-\$).did.	USPAT	2004/07/09 11:36
-	0	((US-6111722-\$ or US-5949623-\$ or US-5528440-\$).did.) and electron	USPAT; US-PGPUB; EPO; JPO	2004/07/09 11:36
-	0	((US-6111722-\$ or US-5949623-\$ or US-5528440-\$).did.) and stencil	USPAT; US-PGPUB; EPO; JPO	2004/07/09 11:37
-	26	"electron beam resist mask"	USPAT; US-PGPUB; EPO; JPO	2004/07/09 11:50

-	7299	"e-beam"	USPAT; US-PGPUB; EPO; JPO	2004/07/09 11:51
-	103	"e-beam" and (gmr mmr magnetoresistive)	USPAT; US-PGPUB; EPO; JPO	2004/07/09 12:00
-	1141	"stencil mask"	USPAT; US-PGPUB; EPO; JPO	2004/07/09 12:00
-	9	"stencil mask" and (gmr mmr magnetoresistive)	USPAT; US-PGPUB; EPO; JPO	2004/07/09 12:08
-	1	5949623.pn. and width	USPAT	2004/07/09 12:09
-	0	5264981.pn. and width	USPAT	2004/07/09 12:09
-	0	5614727.pn. and width	USPAT	2004/07/09 12:09